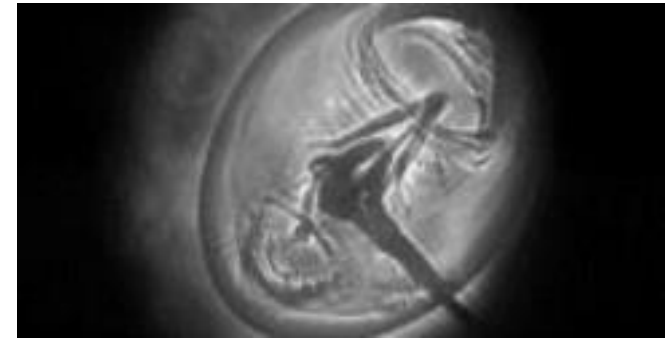
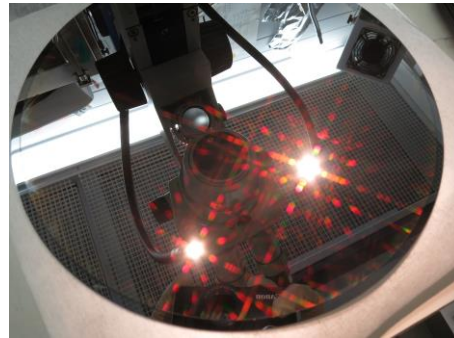
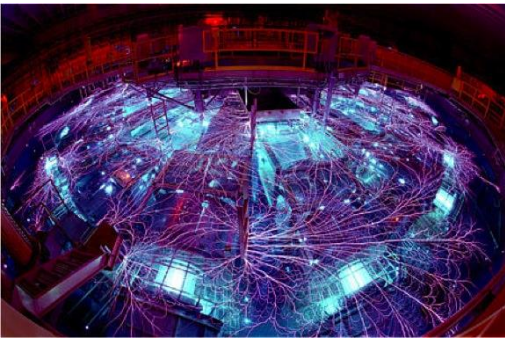


*Exceptional service in the national interest*



# Low-Energy Sensitive Diodes for hCMOS Sensors

Q. Looker, R. Kay, J. Long, G. Robertson,  
M. Sanchez, D. Trotter, J. Porter

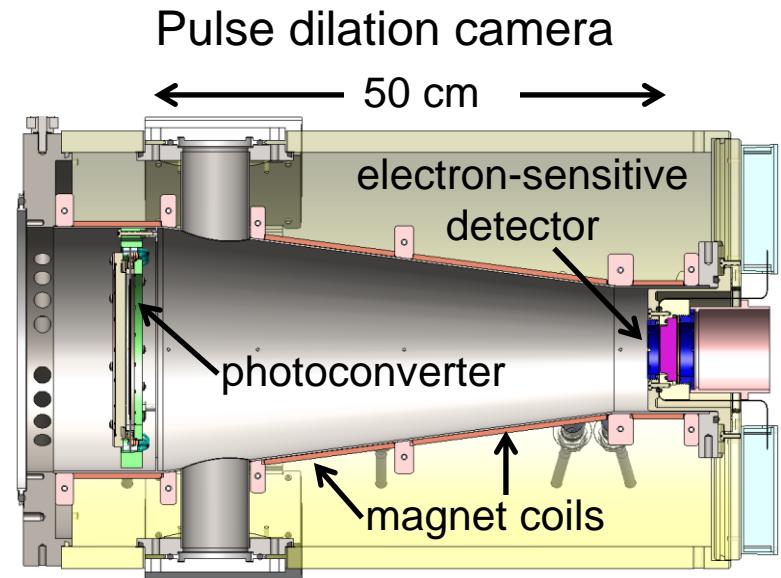
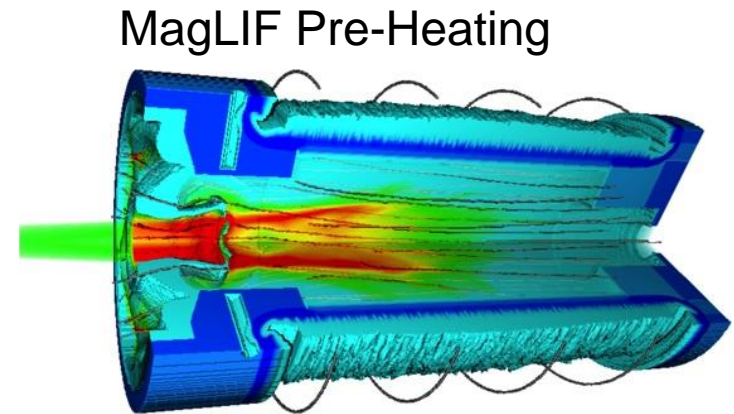
10/6/2015



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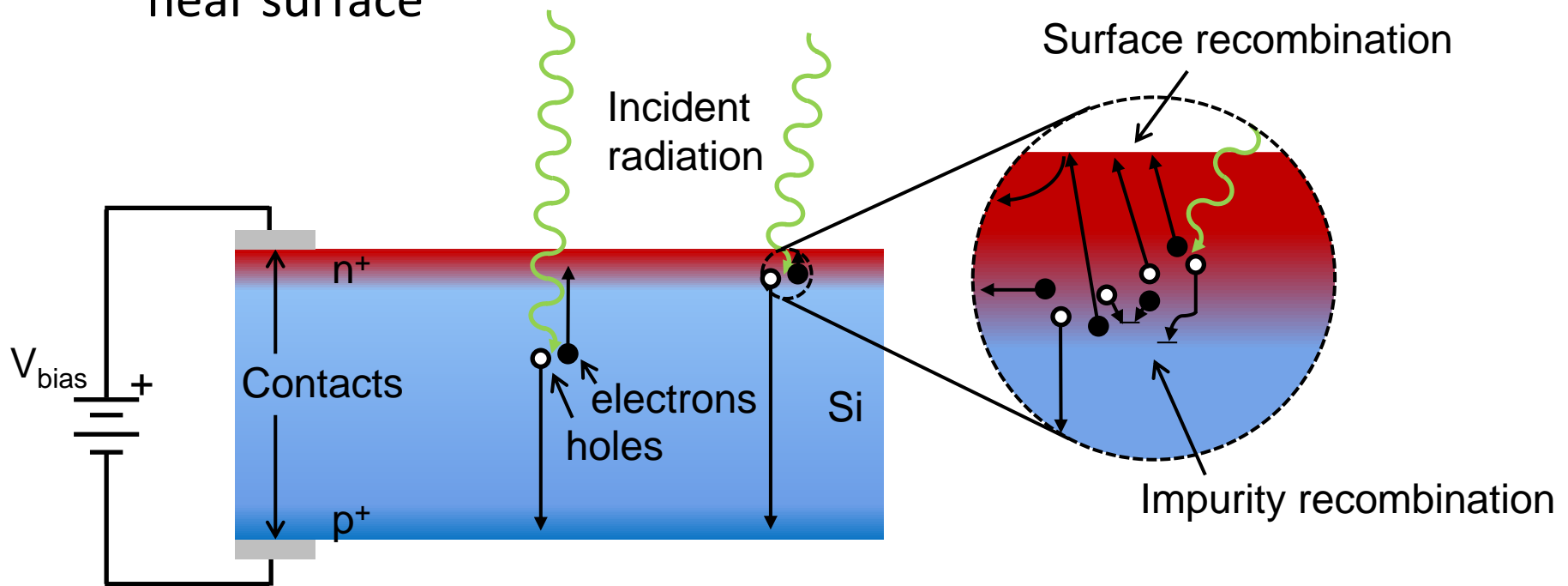
# Pulsed Power Applications Exist for Soft X-Ray and Electron Detectors

- Potential Applications
  - Thermometry on Z shots: soft x-rays 100-600 eV
  - Pulse dilation camera: electrons 2-10 keV
- Si Diodes Advantageous
  - Time-resolved measurements
  - Easily integrated into hCMOS camera
- Current Challenges
  - Current diodes insensitive to photons below  $\sim 700$  eV
  - Low detection efficiency for electrons below about 10 keV



# Silicon Detector Construction Matters

- Detector electrodes sense moving charge
- Maximum signal generally requires complete charge collection
- Reduced charge collection from interactions near surface



# Soft X-Ray Detection is a Shallow Issue

## Issue

- X-Rays 100-1000 eV
- Predominantly photoelectric absorption – energy too high for reflection, too low for Compton scatter
- Extremely short absorption length – detector surface properties dominate
- Dead layer approximation

$$E_{abs} = E_{in} \left[ 1 - e^{-\frac{t_{total}}{l}} \right]$$

$$E_{dl} = E_{in} \left[ 1 - e^{-\frac{t_{dl}}{l}} \right]$$

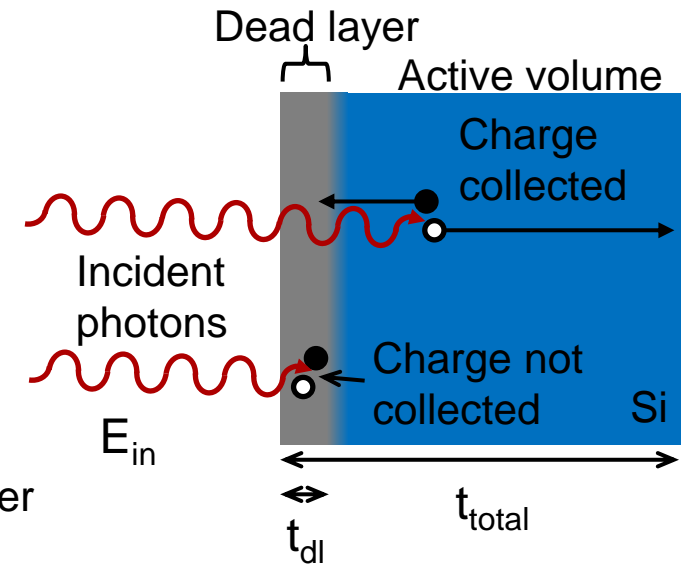
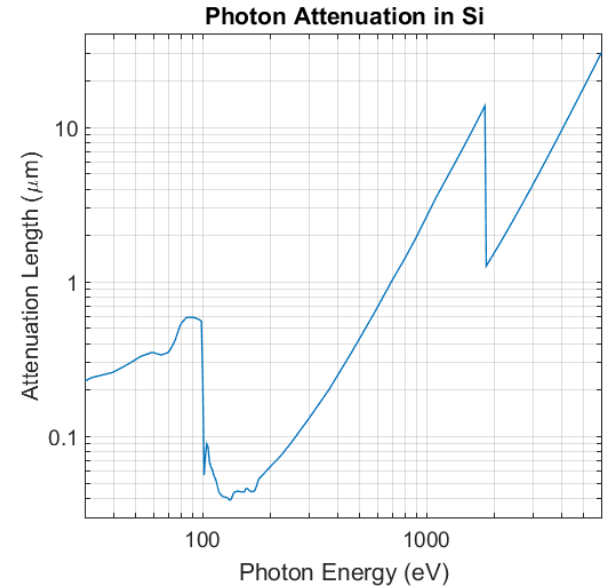
$$\Delta_{dl} = \frac{E_{dl}}{E_{in}}$$

$l$ : photon absorption length

$E_{abs}$ : energy absorbed in diode

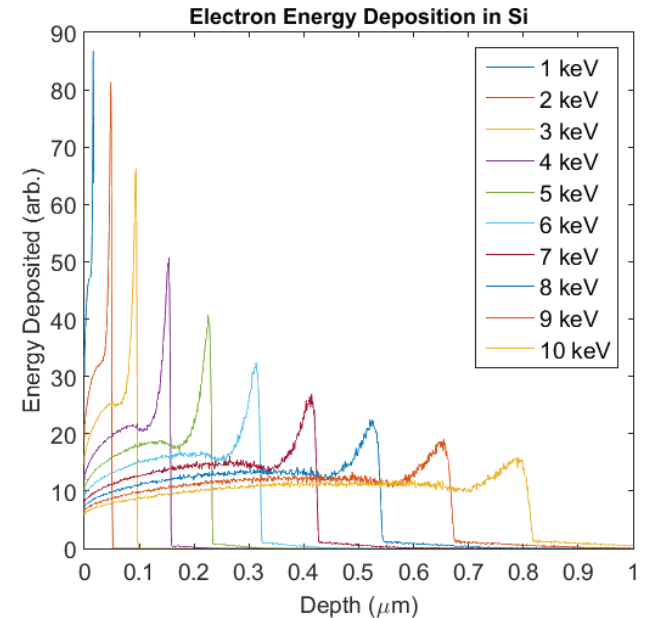
$E_{dl}$ : energy absorbed in dead layer

$\Delta_{dl}$ : dead layer deficit



# Electron Detection adds Backscatter to the Mix

- Electrons 1-10 keV
- Coulomb scattering – continuous energy deposition
- Extremely short absorption depth – dead layer requirements similar to soft X-Ray
- Backscatter also important



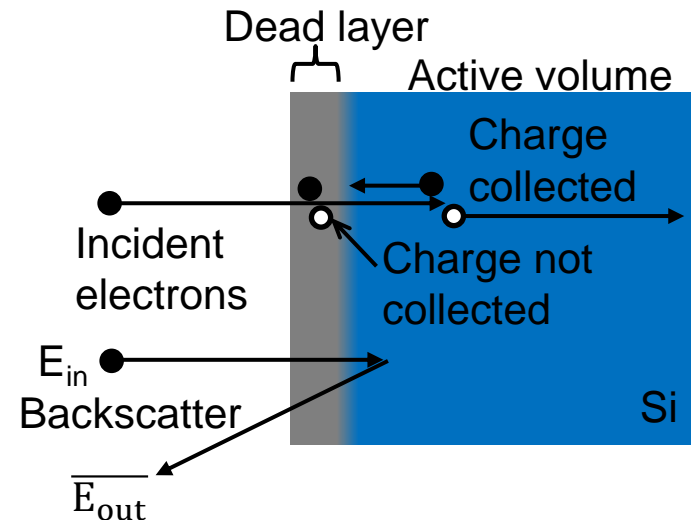
$$\Delta_{bs} = \eta \frac{\overline{E_{out}}}{E_{in}}$$

$\eta$ : backscatter probability

$E_{in}$ : incident electron energy

$\overline{E_{out}}$ : average backscattered electron energy

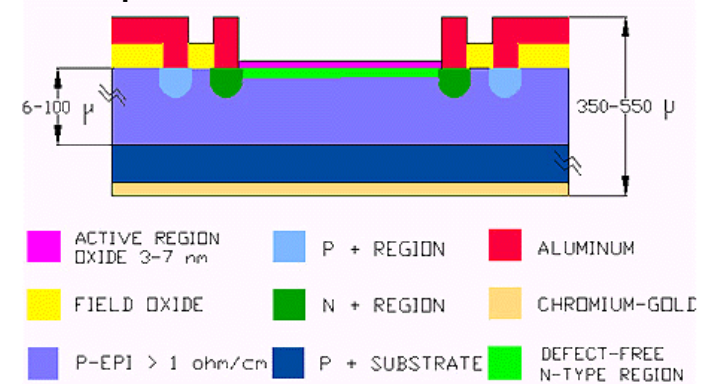
$\Delta_{bs}$ : backscatter deficit



# Existing Technology

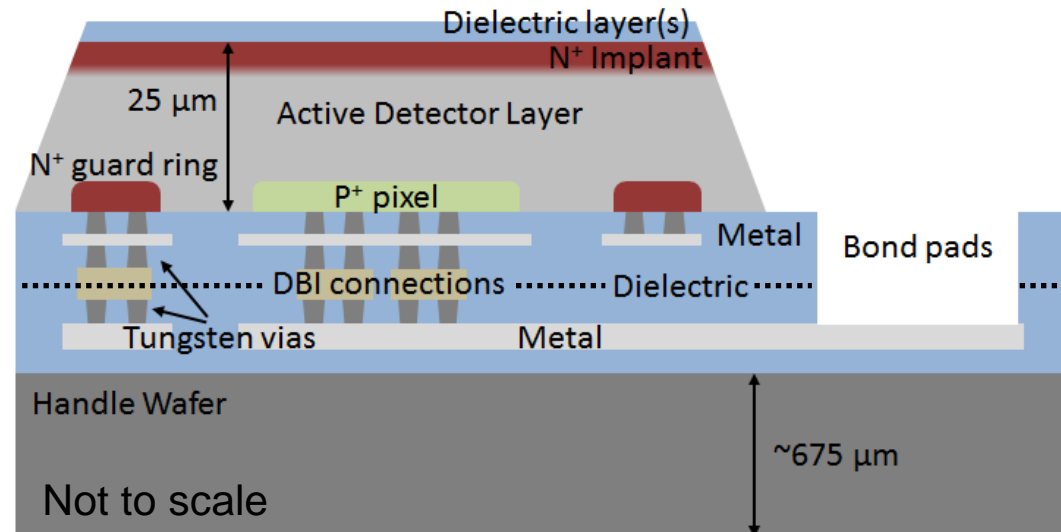
- OptoDiode AXUV models are a common standard
- Need for CMOS compatibility, high fill factor, and wafer real estate drove cameras to hybridization
- Sandia test photodiode utilizes similar technology to hCMOS cameras

## OptoDiode AXUV Series



[www.optodiode.com](http://www.optodiode.com)

## Sandia Test Photodiode



# Electron Sensitivity was Tested Using an SEM

- Responsivity is a general measure of diode sensitivity to a particular radiation type
- DC measurement is well-controlled

$$R = \frac{I_{diode}}{P_{beam}}$$

$R$ : diode responsivity  
 $I_{diode}$ : diode photocurrent  
 $P_{beam}$ : incident beam power  
 $I_{beam}$ : incident beam current  
 $E_{beam}$ : incident beam energy

$$P_{beam} = I_{beam} * E_{beam}$$

$$R_{ideal} = \frac{1}{w}$$

$w$ : electron-hole pair creation energy  
For Si,  $w=3.67\pm 0.02$  eV [1]



www.fei.com

Following [2], three major loss mechanisms:

$$R = R_{ideal} [1 - \Delta_{dl} - \Delta_{bs} - \Delta_{res}]$$

$\Delta_{dl}$ : dead layer absorption  
 $\Delta_{bs}$ : backscatter loss  
 $\Delta_{res}$ : residual loss

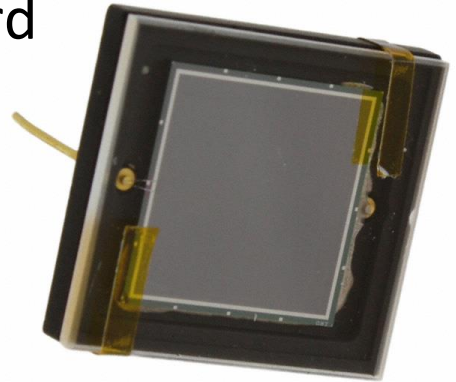
[1] R. Pehl et al., NIM Vol. 59, pp. 44-55 (1968)

[2] H. Funsten et al., IEEE TNS Vol. 44, No. 6, p. 2561 (1997)

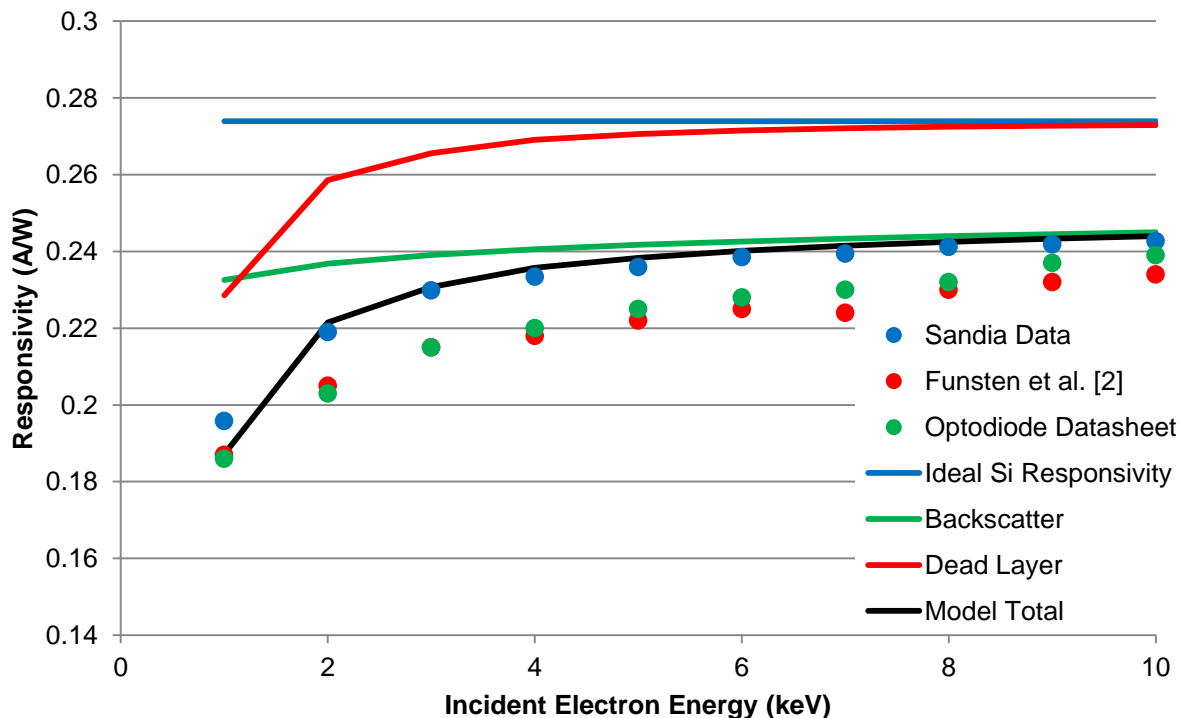


# Method was Benchmarked using Industry Standard

- OptoDiode's AXUV100G is a widely used standard
- Model predicts dead layer and backscatter loss



www.digikey.com



Backscatter based on average energy from [1],  $\eta$  values from [2]

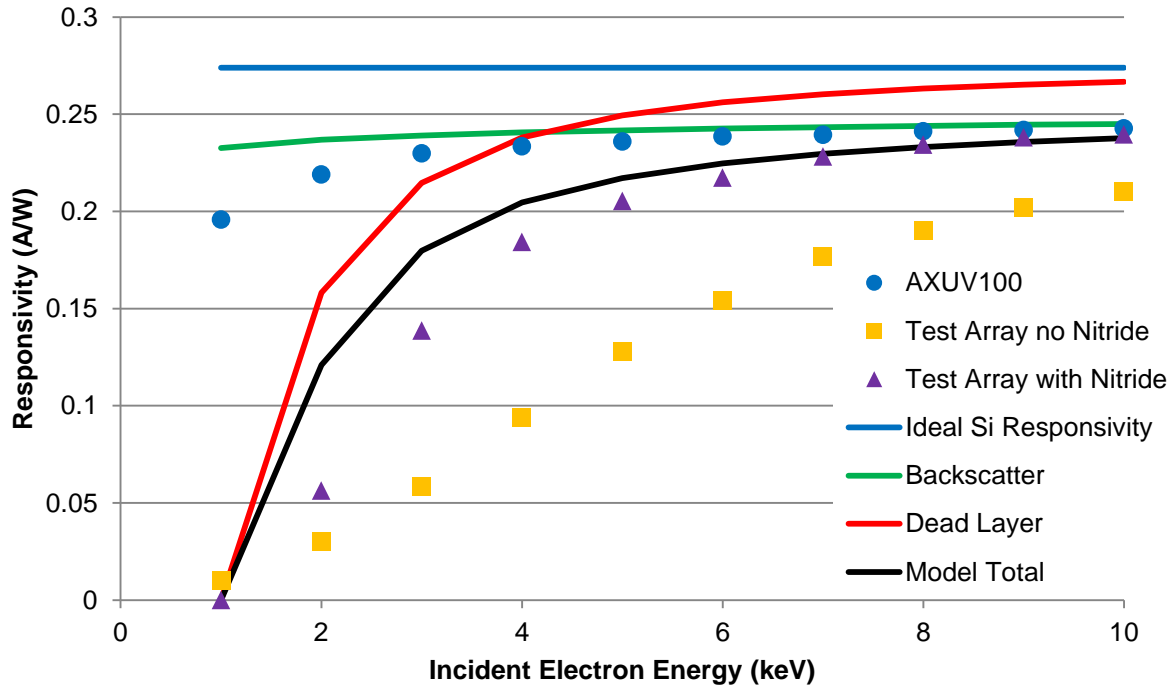
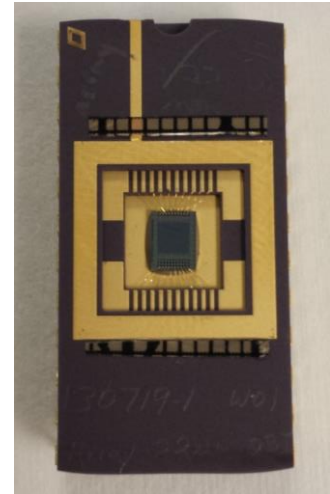
Dead Layer based on 8 nm  $\text{SiO}_2$  with stopping power values from [3]

- [1] H. Funsten et al., IEEE TNS Vol. 44, No. 6, p. 2561 (1997)  
[2] H. Hunger & L. Kuchler, Phys. Stat. Sol. Vol. 56, pp. K45-K48 (1979)  
[3] J. Ashley & V. Anderson, JES Vol. 24, pp. 127-148 (1981)



# Current Generation Diode Array Sensitivity Tested

- Surface passivation adds more dead layer absorption, but apparently reduces surface recombination



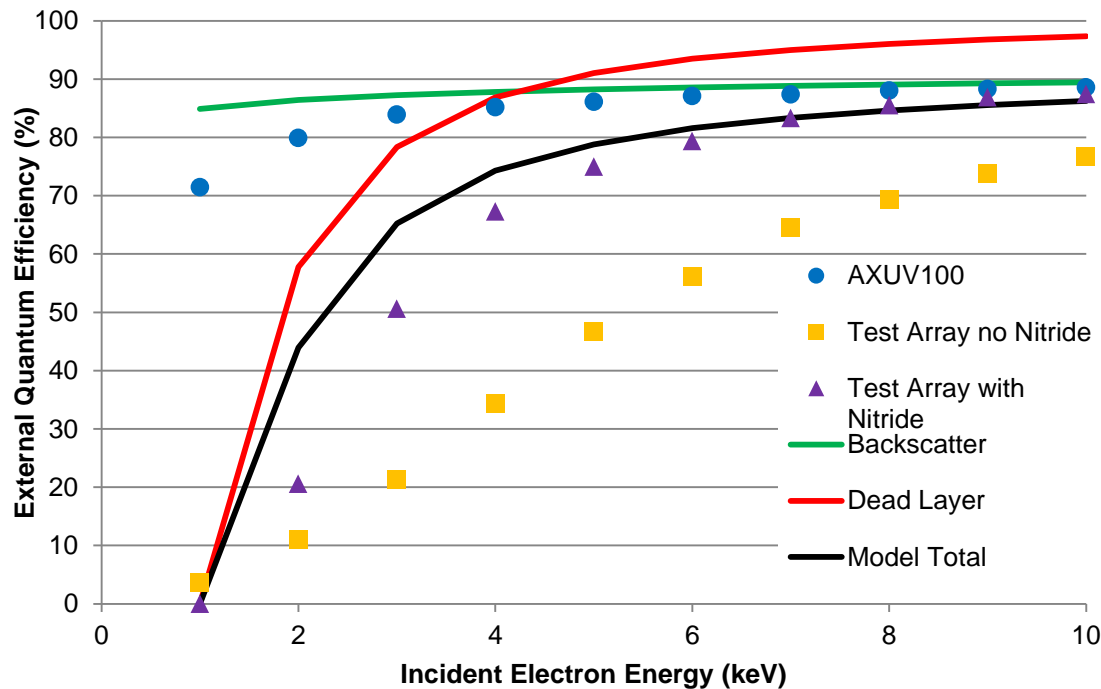
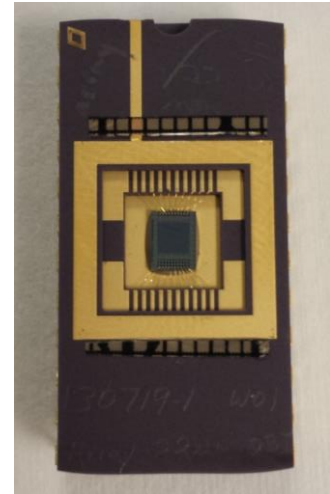
Dead Layer based on  $\text{Si}_3\text{N}_4$  stopping power from [1] and  $\text{SiO}_2$  stopping power values from [2]

[1] NIST Estar, <http://physics.nist.gov/PhysRefData/Star/Text/ESTAR.html>

[2] J. Ashley & V. Anderson, JES Vol. 24, pp. 127-148 (1981)

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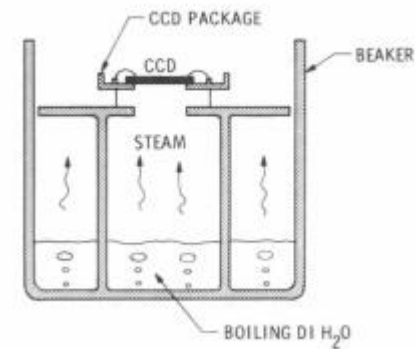
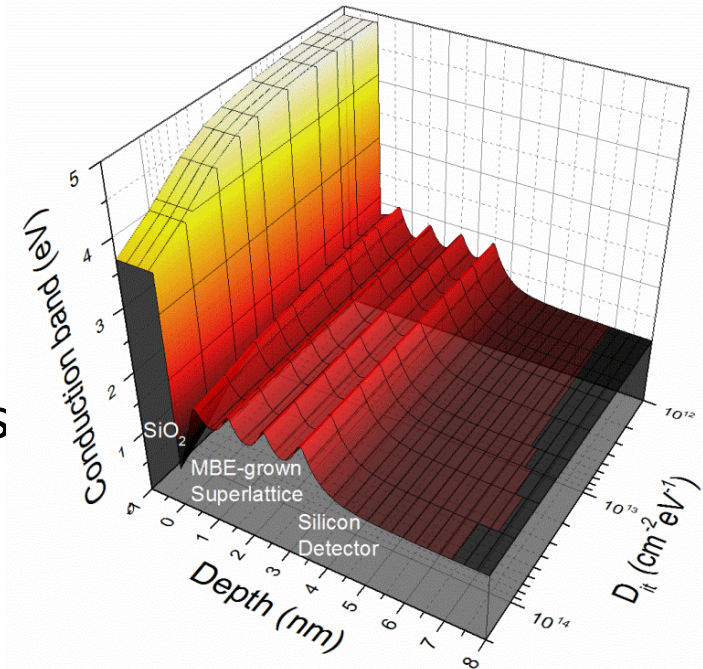
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[1] NIST Estar, <http://physics.nist.gov/PhysRefData/Star/Text/ESTAR.html>

[2] J. Ashley & V. Anderson, JES Vol. 24, pp. 127-148 (1981)

# Path Forward

- hCMOS cameras will incorporate nitride passivation layer
- New discrete diodes will provide test bed for alternative technologies
  - JPL Delta Dope, successfully demonstrated to increase CCD UV sensitivity [1]
  - Univ. of Arizona flash oxide, also demonstrated for UV rays on CCDs [2]
- hCMOS diode arrays will incorporate new findings



[1] Hoenk et al., APL Vol. 61, pp. 1084-1086 (1992)

[2] Janesick et al., Opt. Eng. Vol. 26, pp. 852-863 (1987)